

Class	Subclass
438	787

U.S. UTILITY Patent Application

0121

APPLICATION NO. 09/632425	CONT/PRIOR	CLASS 438	SUBCLASS 787	ART UNIT 2889	EXAMINER HEICDAY
------------------------------	------------	--------------	-----------------	------------------	---------------------

APPLICANTS
Fabrice Gaigar
Frederic Gaillard

TITLE
Process for depositing a porous, low dielectric constant silicon
oxide film

PTO-2040
12/99

<p>INVENTOR</p> <p>BY</p> <p>ATTORNEY</p>	<p>DATE</p> <p>FILED</p> <p>OFFICE</p> <p>U.S. PATENT & TRADEMARK OFFICE</p>
---	--

Information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Patent & Trademark Office. Information outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.

PTO-2040

FILED WITH: ☐ DISK (CR) ☒ PAPER